



US00D832941S

(12) **United States Design Patent**  
**Wu**

(10) **Patent No.:** **US D832,941 S**  
(45) **Date of Patent:** **\*\* Nov. 6, 2018**

- (54) **MASK**
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- (72) Inventor: **Chun-Hung Wu**, New Taipei (TW)
- (\*\*) Term: **15 Years**
- (21) Appl. No.: **29/572,892**
- (22) Filed: **Aug. 1, 2016**
- (51) **LOC (11) Cl.** ..... **21-03**
- (52) **U.S. Cl.**  
USPC ..... **D21/660**
- (58) **Field of Classification Search**  
USPC ..... D21/576-579, 585, 588, 593, 594, 612,  
D21/621, 623, 625, 626, 627, 631, 633,  
D21/635, 639, 645, 649, 658, 659-661  
CPC ..... A42B 3/20; A42B 3/225; A41D 13/11;  
A41D 13/1107  
See application file for complete search history.

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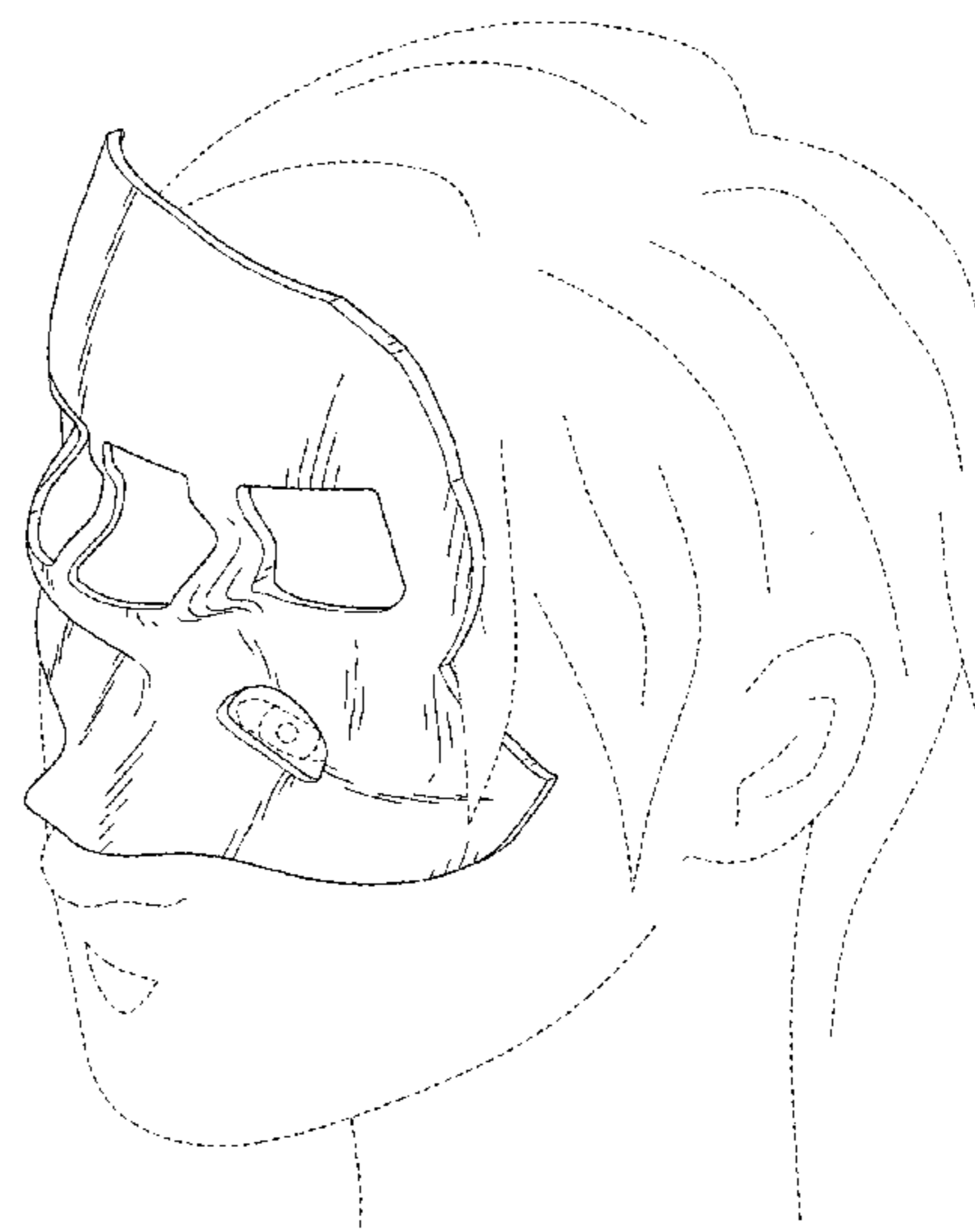
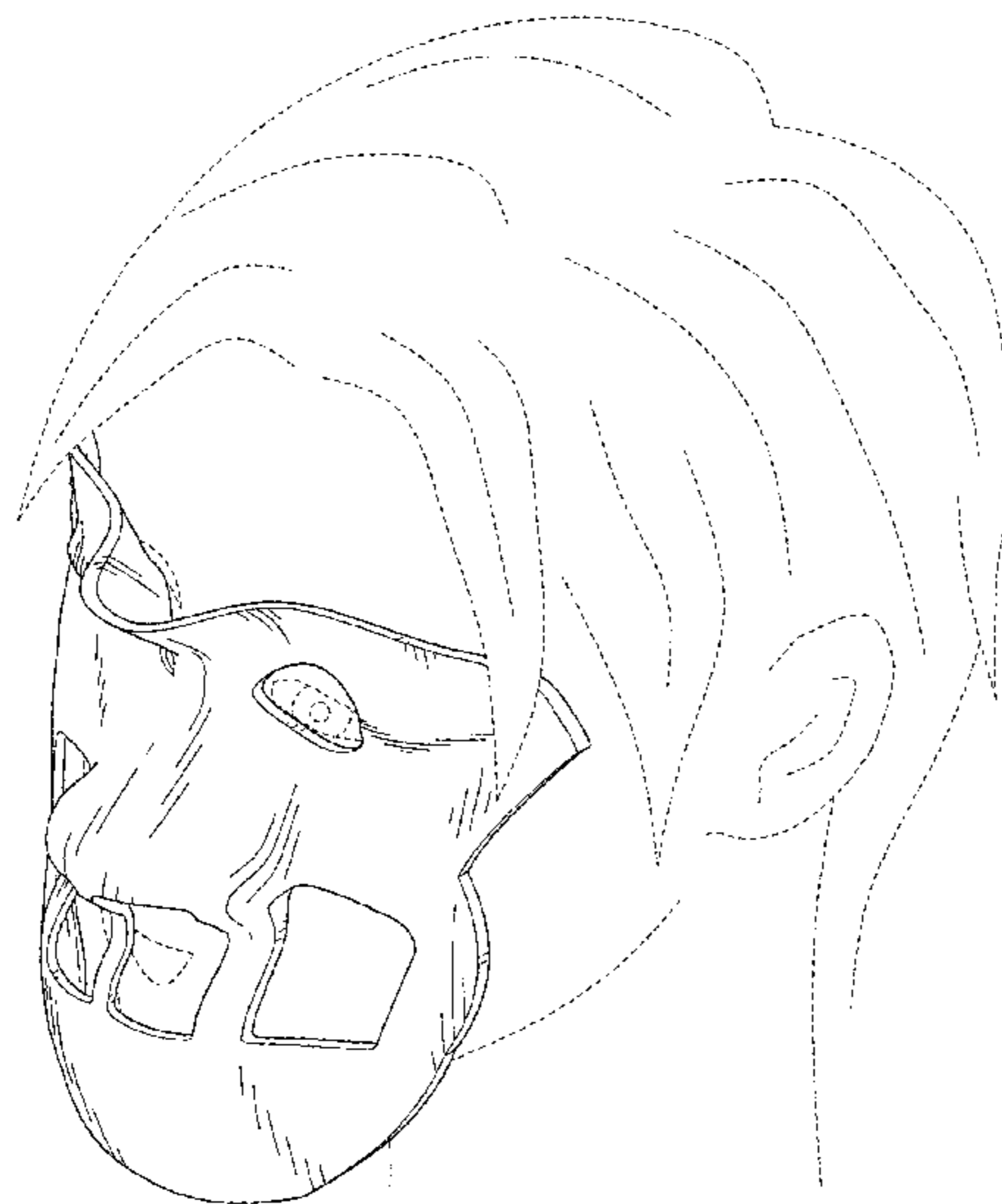
(57) **CLAIM**

The ornamental design for a mask, as shown and described.

**DESCRIPTION**

FIG. 1 is a perspective view of a mask, showing my new design;  
FIG. 2 is a front elevational view thereof in which the profile lines 8-8 and 9-9 herein form no part of the claimed design;  
FIG. 3 is a rear elevational view thereof;  
FIG. 4 is a left elevational view thereof;  
FIG. 5 is a right elevational view thereof;  
FIG. 6 is a top plan view thereof;  
FIG. 7 is a bottom plan view thereof;  
FIG. 8 is a cross-sectional view along line 8-8 shown in FIG. 3;  
FIG. 9 is a cross-sectional view along line 9-9 shown in FIG. 3;  
FIG. 10 is the mask in condition of use, where it is adapted to fit a lower portion of a human's face; and,  
FIG. 11 is the mask in condition of use, where it is adapted to fit an upper portion of the human's face.  
The broken line within figure drawings represents unclaimed environment only, and forms no part of the claimed design.

**1 Claim, 9 Drawing Sheets**



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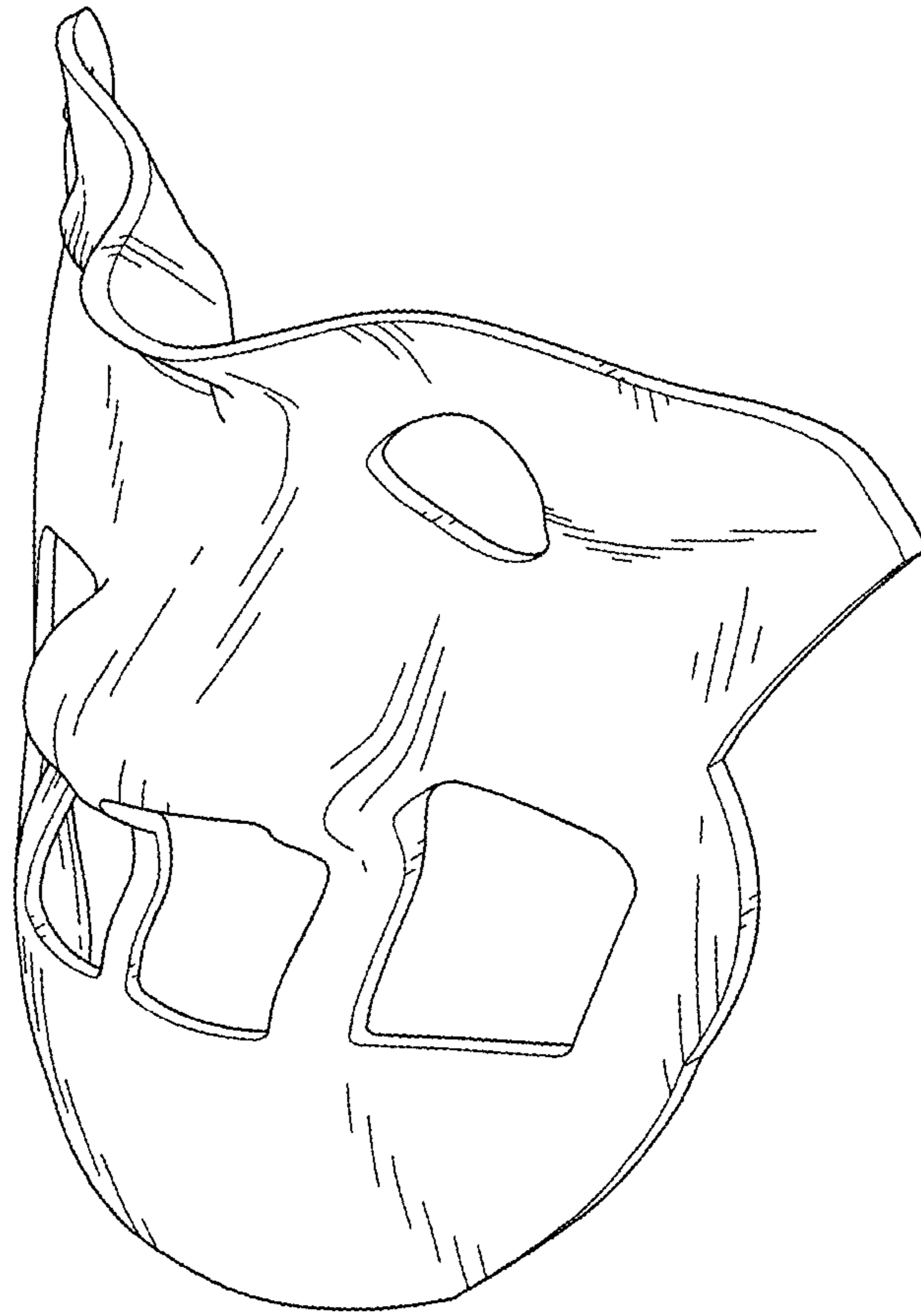


FIG.1

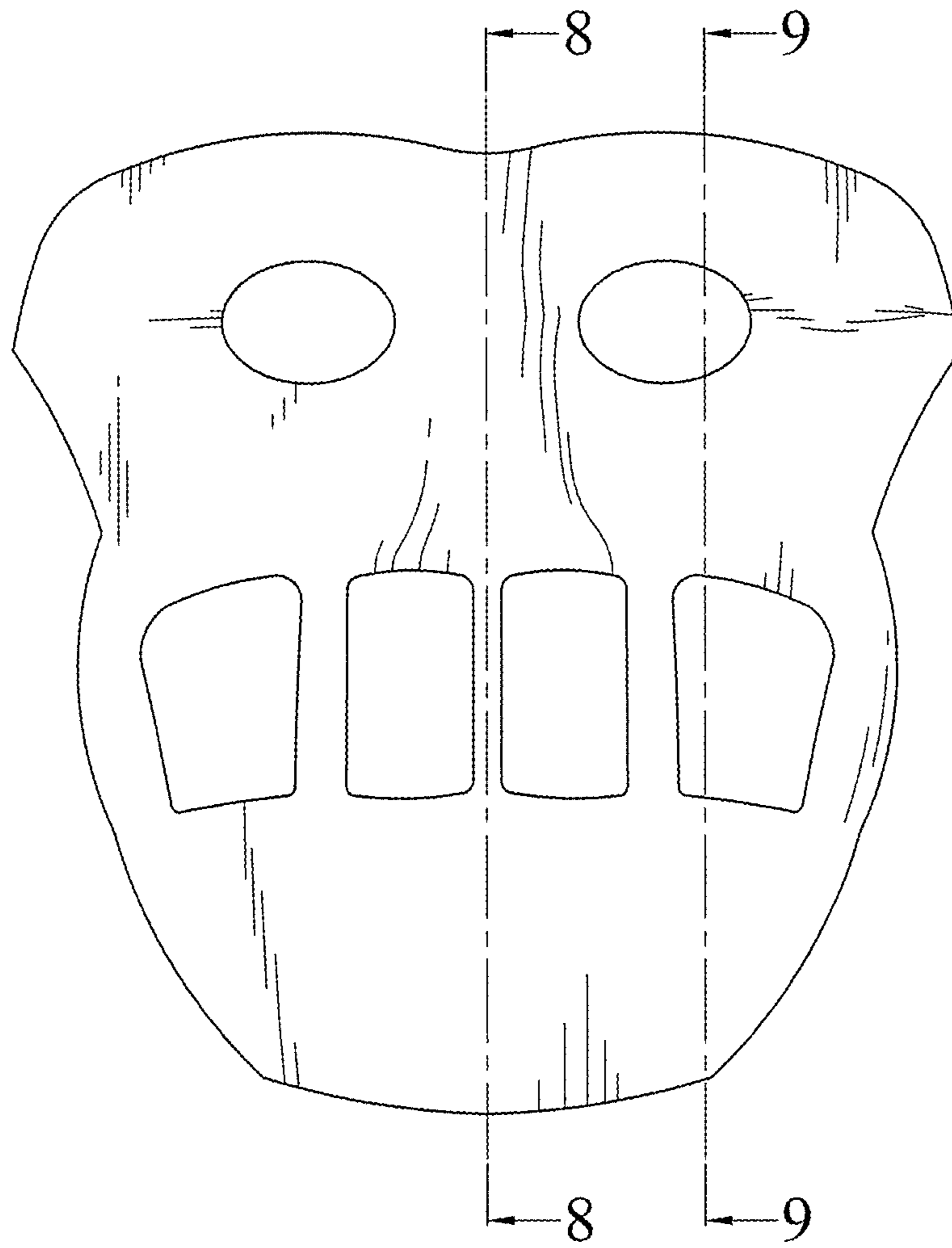


FIG.2

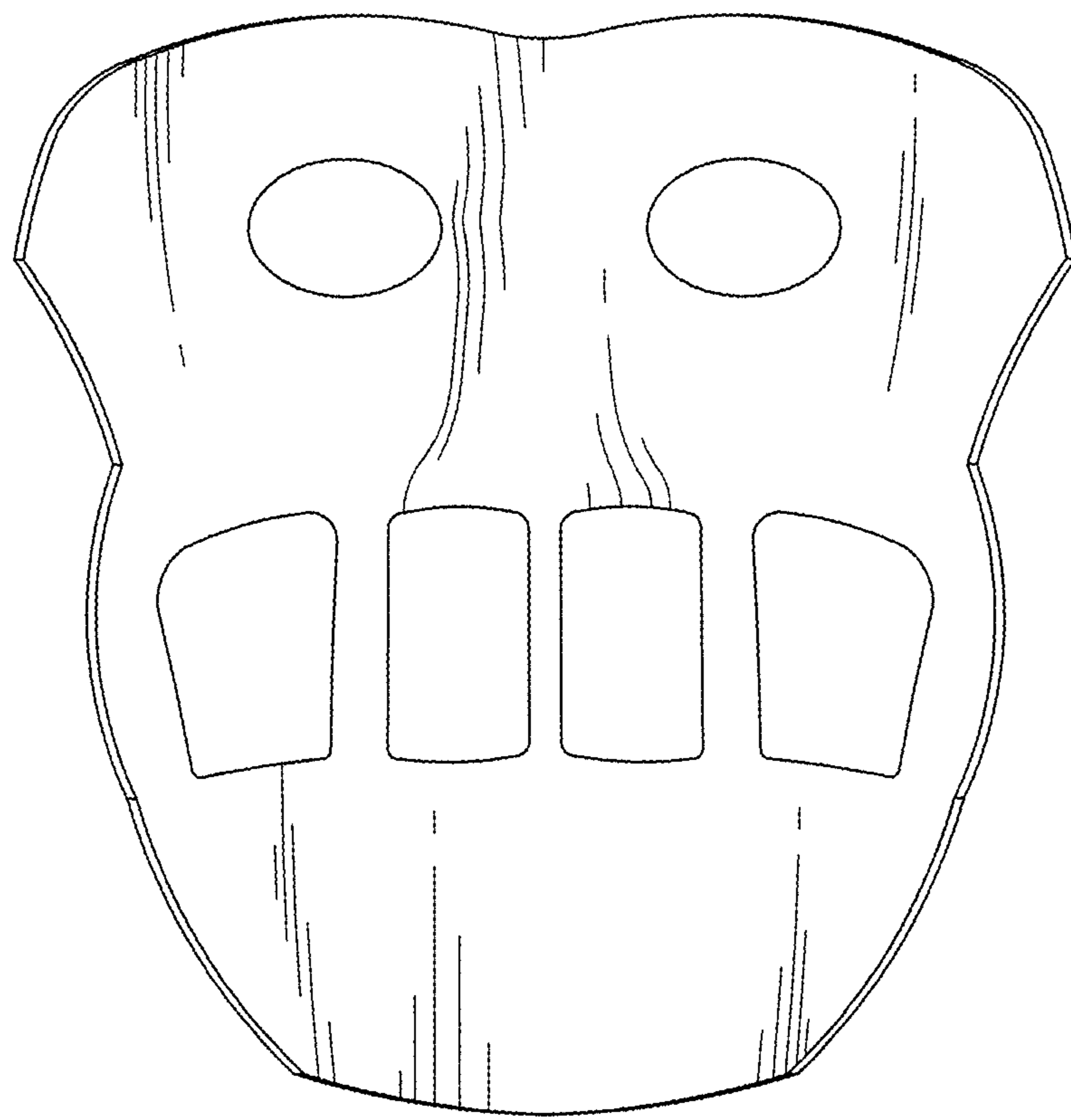


FIG.3

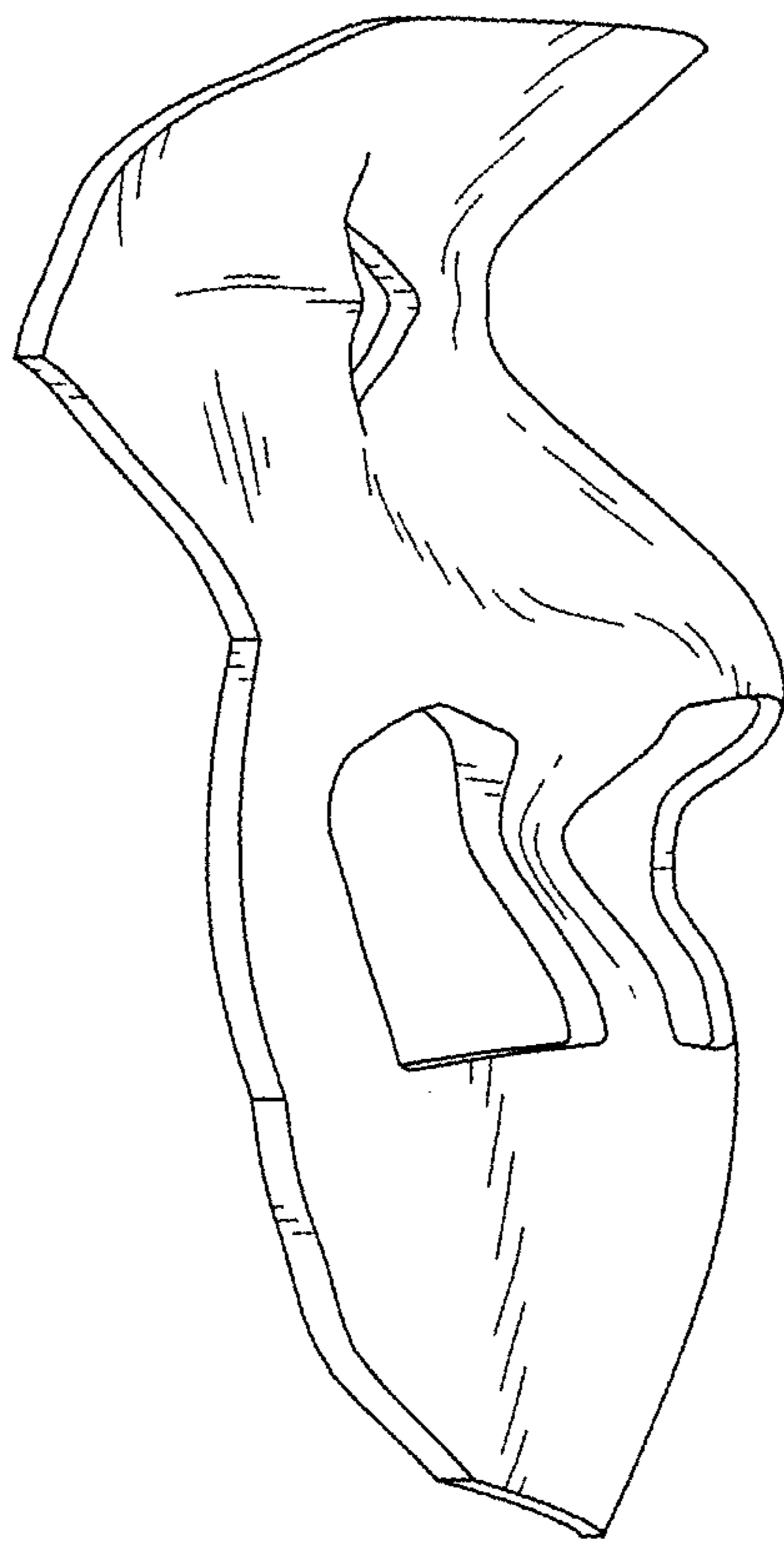


FIG.4

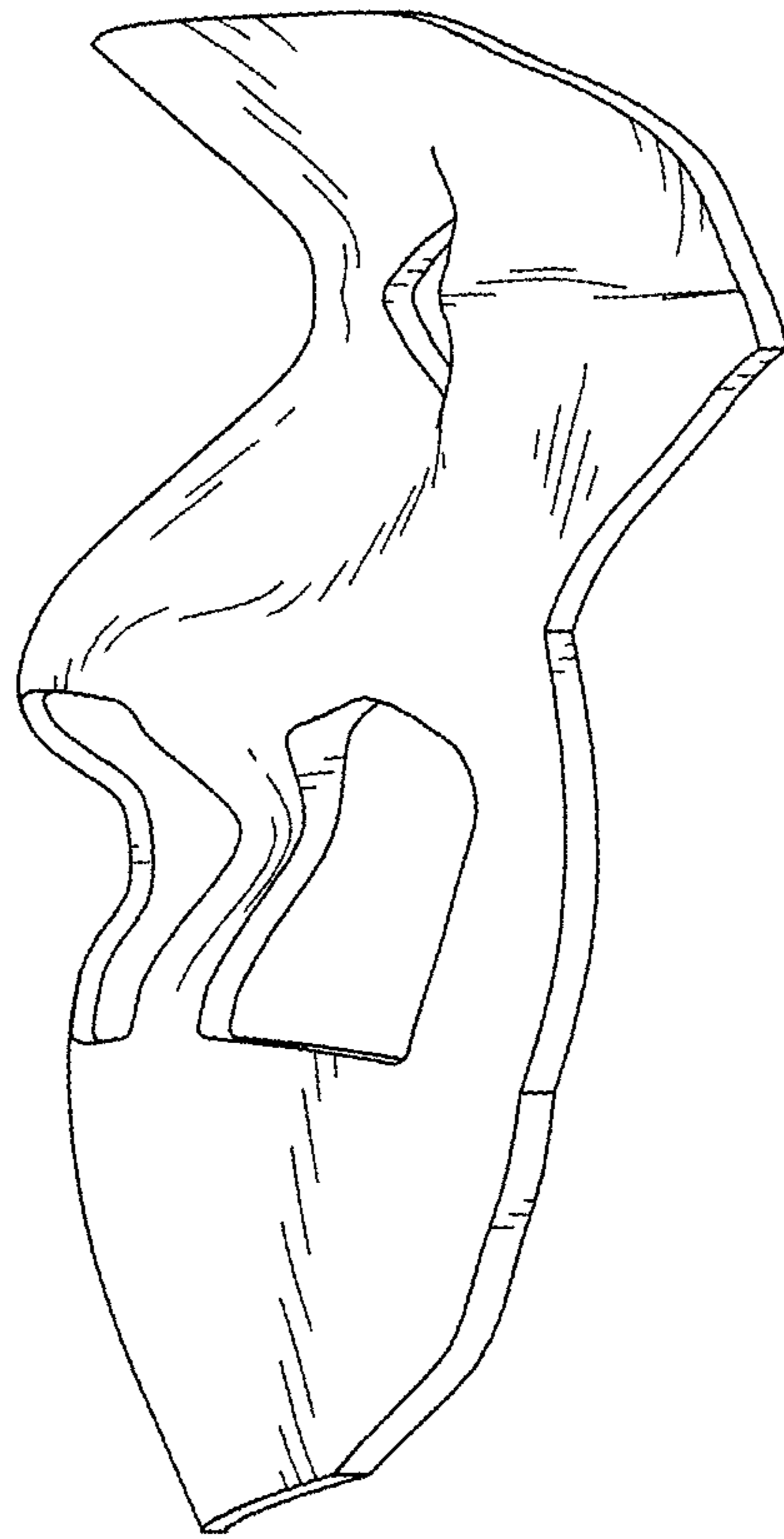


FIG.5

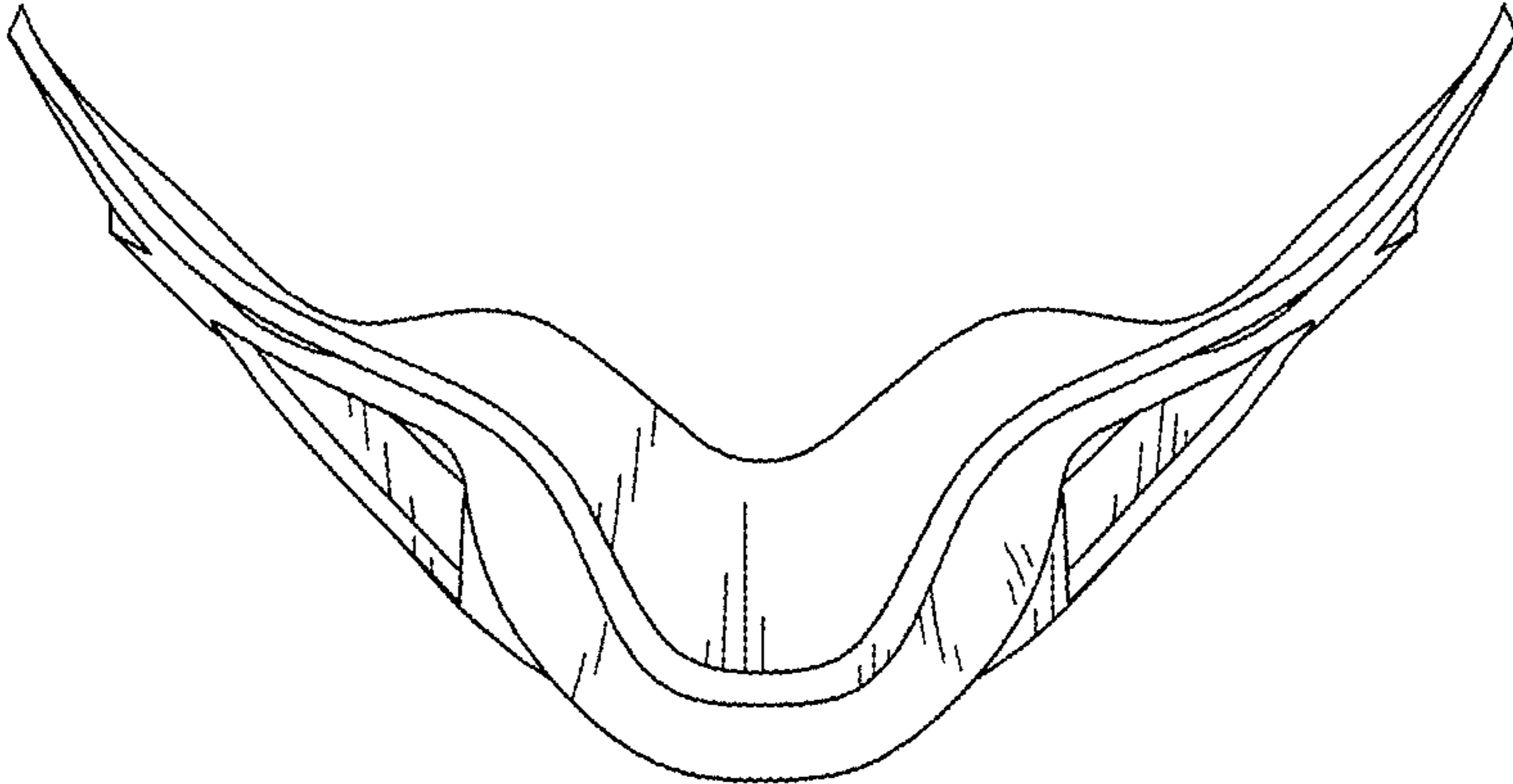


FIG. 6

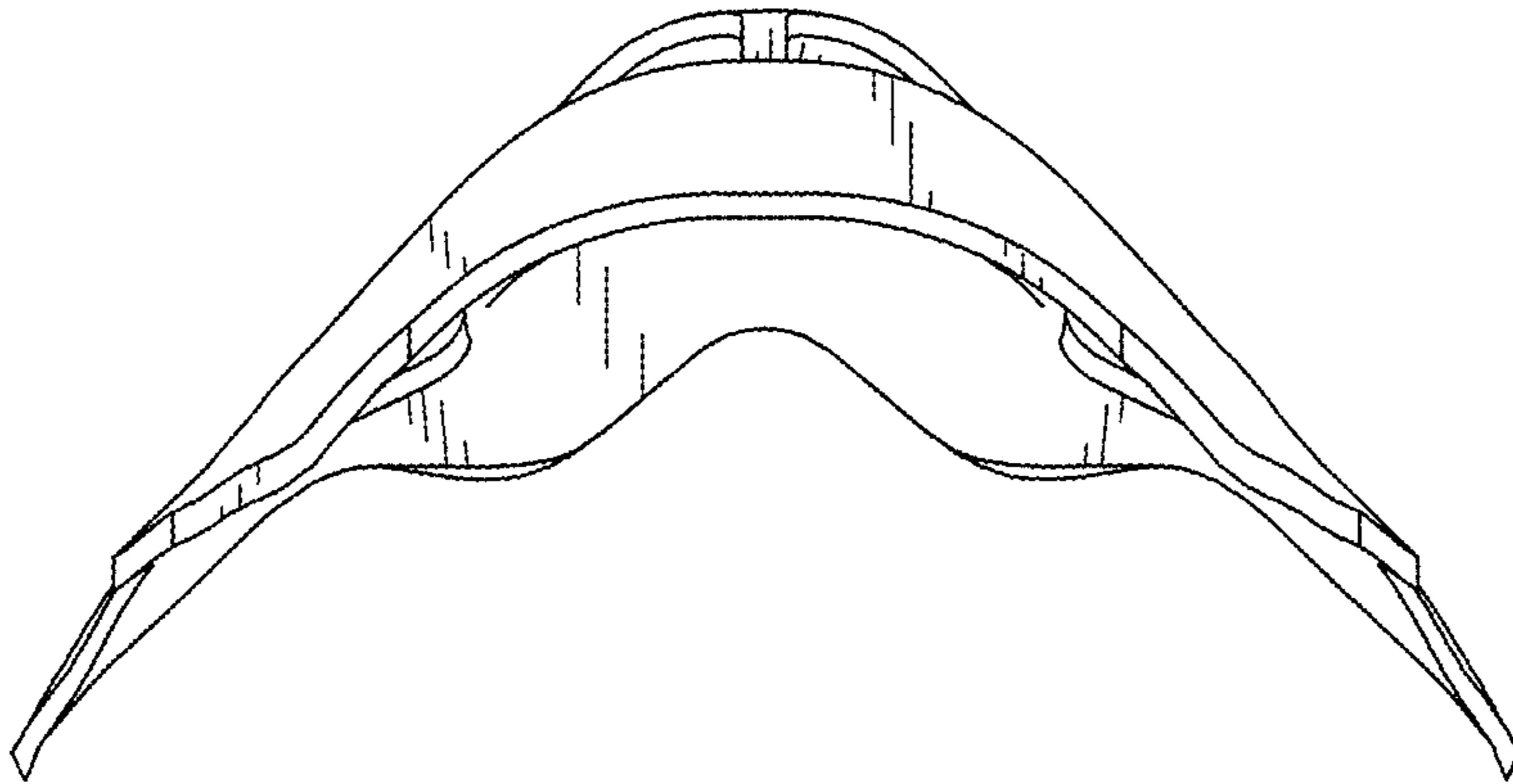


FIG. 7



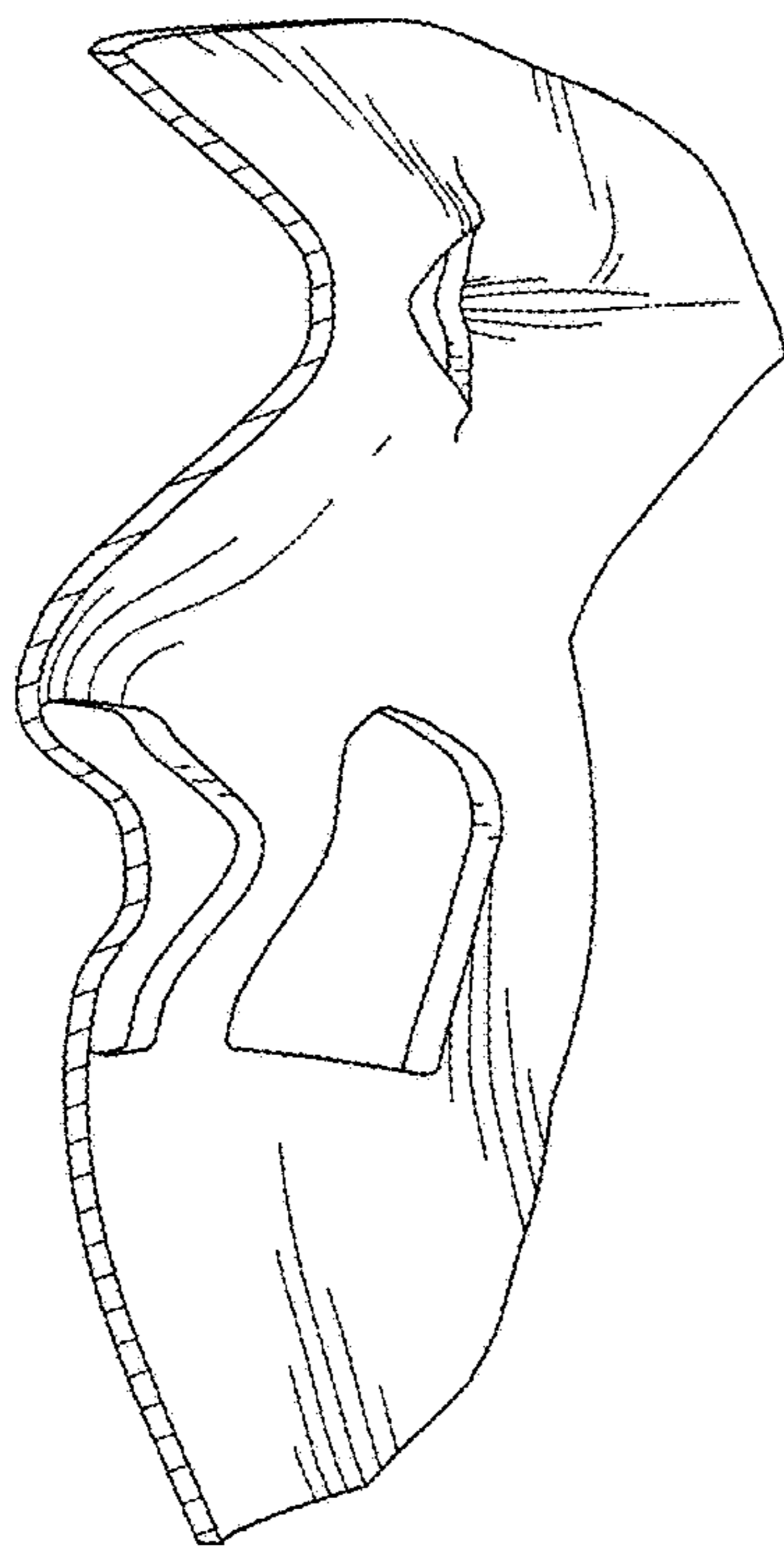


FIG. 8

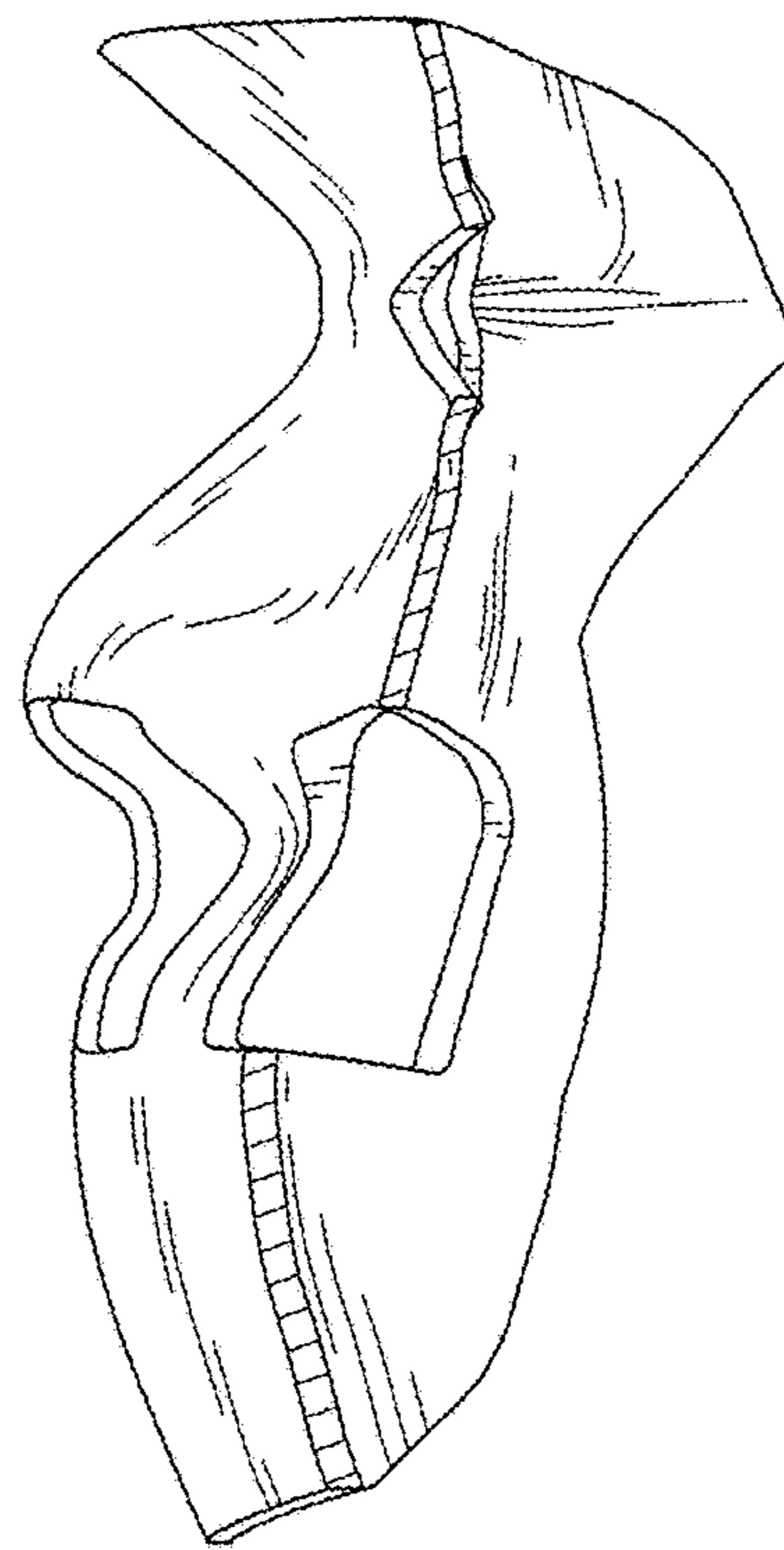


FIG. 9

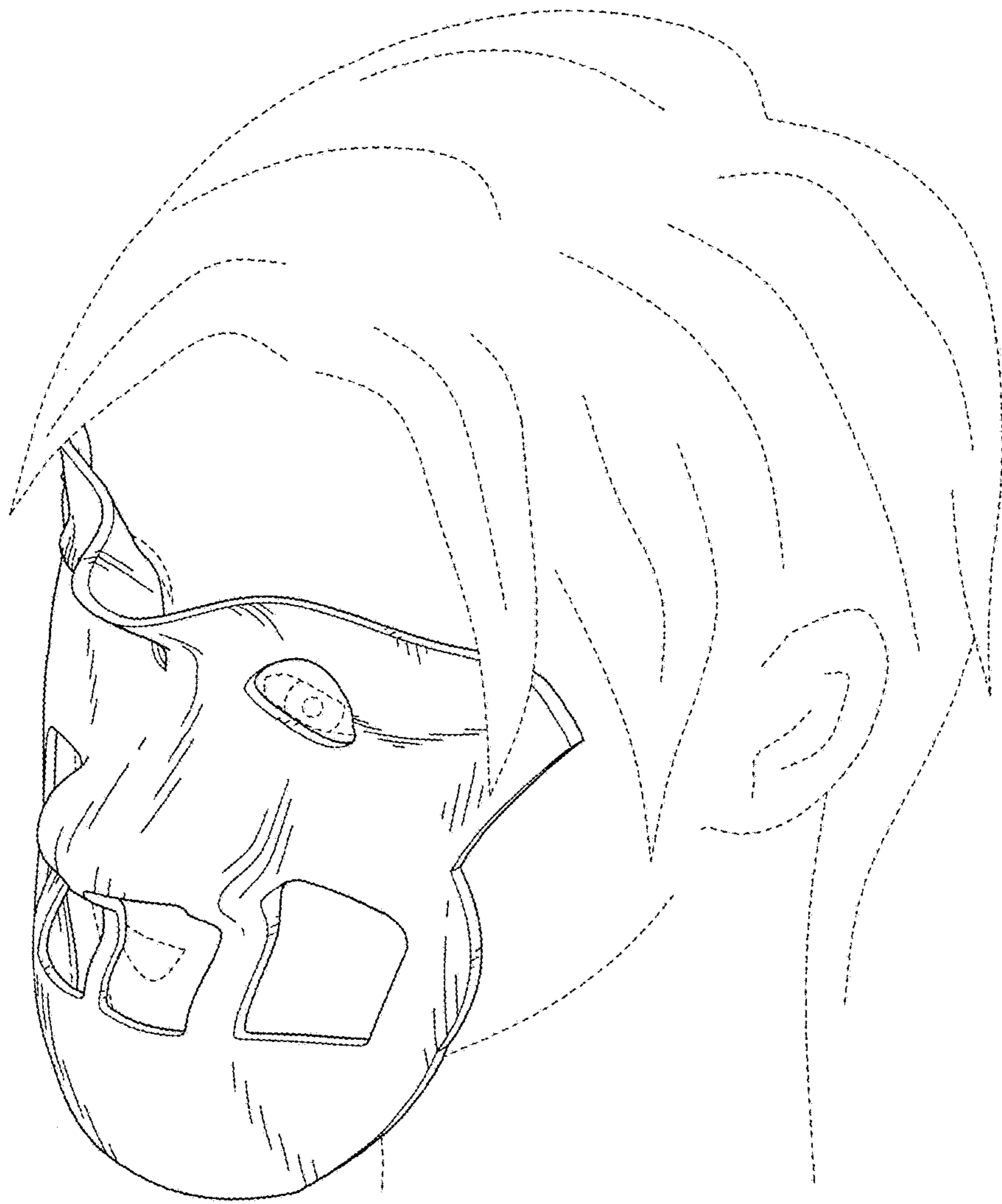


FIG.10

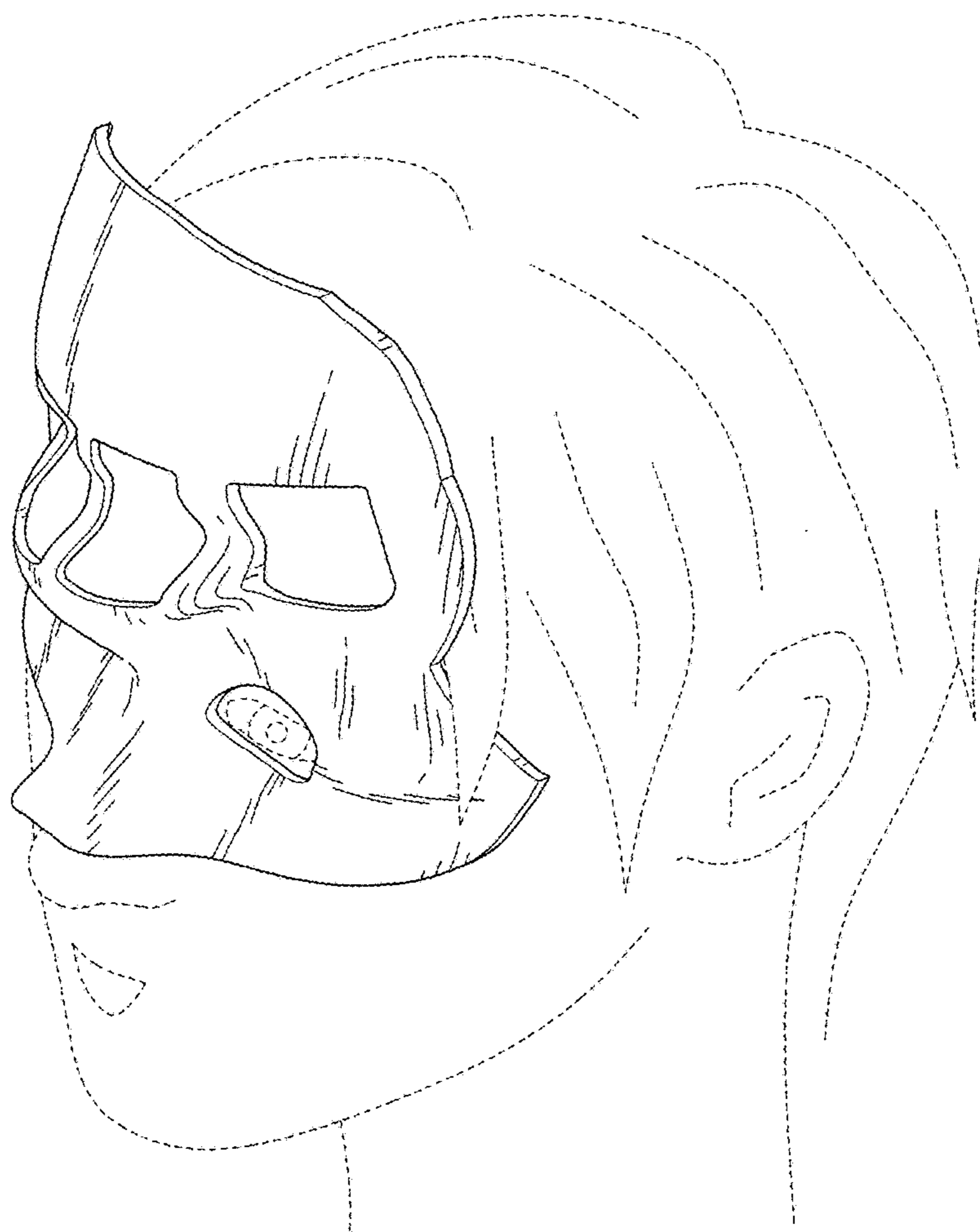


FIG.11